IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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SF TEW 12811

Justin K. Brask et al.

Art Unit:

2811

Serial No.:

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Examiner:

Ori Nadav

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P16709

For:

Forming a High Dielectric Constant

Film Using Metallic Precursor

Assignee:

Intel Corporation

Mail Stop AF Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

REPLY TO FINAL REJECTION

Sir:

In response to the final rejection mailed March 30, 2005, reconsideration is requested in view of the following remarks.

Date of Deposit: April 18, 2005
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450